

N THE UNITED STATES PATENT AND TRADEMARK OFFICE

application of: Zhu et al.

Attorney Docket No.:

NOVLP090/NVLS-002888

Application No.: 10/733,858

Examiner: Not yet assigned

Filed: December 10, 2003

Group: 2812

Title: BIASED H2 ETCH PROCESS IN

DEPOSTION-ETCH-DEPOSITION GAP

Confirmation No. 7860

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CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as first-class mail on September 17, 2004 in an envelope addressed to the Commissioner for Patents, P.O. Box

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INFORMATION DISCLOSURE STA

37 CFR §§1.56 AND 1.97(b)

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

The references listed in the attached PTO Form 1449, may be material to examination of the above-identified patent application. Applicants submit these references in compliance with their duty of disclosure pursuant to 37 CFR §§1.56 and 1.97. The Examiner is requested to make these references of official record in this application.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

This Information Disclosure Statement is: (i) filed within three (3) months of the filing date of the above-referenced application, (ii) believed to be filed before the mailing date of a first Office Action on the merits, or (iii) believed to be filed before the mailing of a first Office Action after the filing of a Request for Continued Examination under §1.114. Accordingly, it is believed that no fees are due in connection with the filing of this Information Disclosure Statement. However, if it is determined that any fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 500388 (Order No. NOVLP090).

Respectfully submitted,
BEYER WEAVER & THOMAS, LLP

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P.O. Box 778 Berkeley, CA 94704-0778

Form 1449 (Modified)	Atty Docket No. NOVLP090/NVLS-2888	Application No.: 10/733,858
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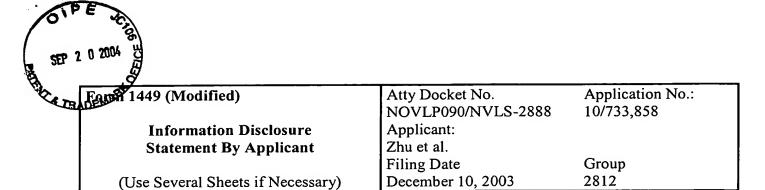
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Examiner		Litation considered. Draw line through citation if not in conformance and

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



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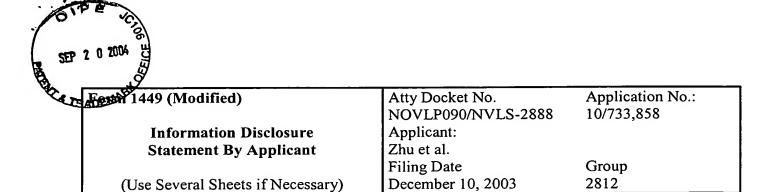
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